44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.

45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.

46. The method of claim 1 wherein the film comprises a moldable polymer.

47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.

48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.

49. The method of claim 48 wherein the film is a sol.

50. The method of claim 1 wherein the film comprises microfibers.

51. The method of claim 1 wherein the film comprises a multilayer of films.

52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.

53. The method of claim 1 wherein the substrate comprises a single crystal material.

54. The method of claim 1 where in the substrate comprises an amorphous material.

55. The method of claim 1 where the substrate comprises a composite material.

56. The method of claim 1 where the substrate comprises a multilayer substrate.

57. The method of claim 1 wherein the pattern in the mask material is transferred to one layer of a multilayer film.

58. The method of claim 1 wherein the pattern in the mask material is more than one layer of a multilayer film.

59. The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is used as a mask to pattern the underlying layers in the multilayer film.

CONCLUSION

Claims 2-41 have been cancelled without prejudice, and new claims 42-59 have been added. Claims 1 and 42-59 are pending in this application.

The Examiner is invited to call Applicant's attorney (612-359-3261) if there are any questions concerning this application.

Respectfully submitted,

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This paper or fee is being deposited on the date indicated above with the United States Postal Service pursuant to 37 CFR 1.10, and is addressed to The Commissioner for Patents, Box Patent Application, Washington, D.C. 20231.

Clean Version of Pending Claims

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42. The method of claim 1 wherein the film comprises a material that passes from a flowing state to a non-flowing state during the molding process.

43. The method of claim 42 wherein the film comprises a thermoplastic, hardenable or curable material.

44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.

45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.

46. The method of claim 1 wherein the film comprises a moldable polymer.

47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.

48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.

cont

49. The method of claim 48 wherein the film is a sol.

50. The method of claim 1 wherein the film comprises microfibers.

51. The method of claim 1 wherein the film comprises a multilayer of films.

52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.

53. The method of claim 1 wherein the substrate comprises a single crystal material.

54. The method of claim 1 where in the substrate comprises an amorphous material.

55. The method of claim 1 where the substrate comprises a composite material.

56. The method of claim 1 where the substrate comprises a multilayer substrate.

57. The method of claim 1 wherein the pattern in the mask material is transferred to one layer of a multilayer film.

58. The method of claim 1 wherein the pattern in the mask material is more than one layer of a multilayer film.

59. The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is used as a mask to pattern the underlying layers in the multilayer film.

Docket No. 00600.426US2 U of M Docket No. 98087
WD # 406147.wpd

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RELATED APPLICATIONS

This application is a divisional of U.S. Patent Application Serial No. 09/107,006, filed June 30, 1998, which claims priority to U.S. Patent No. 6,772,905, issued June 30, 1998.